

2010 International Workshop on EUV Lithography

**June 23, 2010 ■ Makena Beach Golf Resort
■ Maui, Hawaii ■**

AWARD CEREMONY

Organized by



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Student Awards

- Student Awards created to encourage student participation - Presented to all students presenting a paper in the 2010 EUVL Workshop
- Three awards to be presented:
 - Analysis of Carbon Contamination on EUV Mask using CSM / ICS (Mask-1), **Jae-Uk Lee, *Hanyang University***
 - An Investigation of Flare Value at Pattern Edge Region in EUVL (Resist -5), **Kangyoo Song, *Pohang University of Science and Technology***
 - Counting Outgassing Molecules (Contamination-5), **Chih-H. Shao, *National University of Kaohsiung***

Outstanding Achievement Award

- The *Outstanding Achievement Award* is presented to a supplier for outstanding contributions to the development of EUVL technology and EUVL infrastructure.
- The *2010 Outstanding Achievement Award* is presented to ASML (Dr. Jos Benschop) for the development of EUVL Scanner Technology and contributions to the EUVL Infrastructure.

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Lifetime Achievement Award

- The *Lifetime Achievement Award* is presented to an individual / organization for lifetime contributions to the development of EUV Lithography.
- *The 2010 Lifetime Achievement Award* is presented to Dr. Obert Wood, for his pioneering work and contributions to the development of EUVL for over twenty-five years.

